Substitute	Form	PTO-1449
(Modified)		

U.S. Department of Commerce Patent adt Trademark Office

Attorney's Docket No. 18239-023US1

Application No. 10/597,806

by Applicant (Use several sheets if necessary)

Applicant Bernhard Kneer et al.

Filing Date

Group Art Unit

(37 CFR §1.98(b))

August 8, 2006

3722

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Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
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Information Disclosure Statement by Applicant		Applicant Bernhard Kneer et al.		
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